



Nafion Passivation of c-Si Surface and Edge for Electron Paramagnetic Resonance

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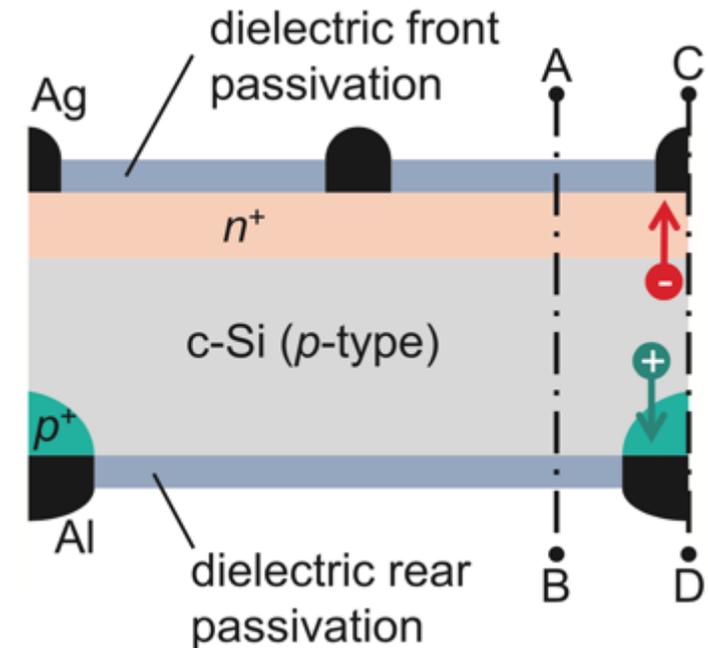
Golden, Colorado, United States

WCPEC 2022

NREL/PR-5900-82881

Bulk Silicon Study Requires Effective Surface Passivation

- Conventional passivation layers require high T processes
 - SiN_x , SiO_x , Al_2O_3 , *a*-Si
- Negative bulk effects from elevated temperatures:
 - $>850\text{ }^\circ\text{C}$: creates oxygen precipitates
 - $250\text{--}450\text{ }^\circ\text{C}$: activates bulk recombination centers, H diffusion, impurity gettering
- Time and energy-consuming



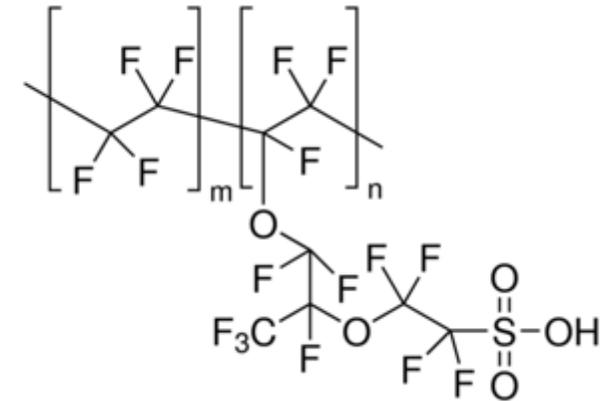
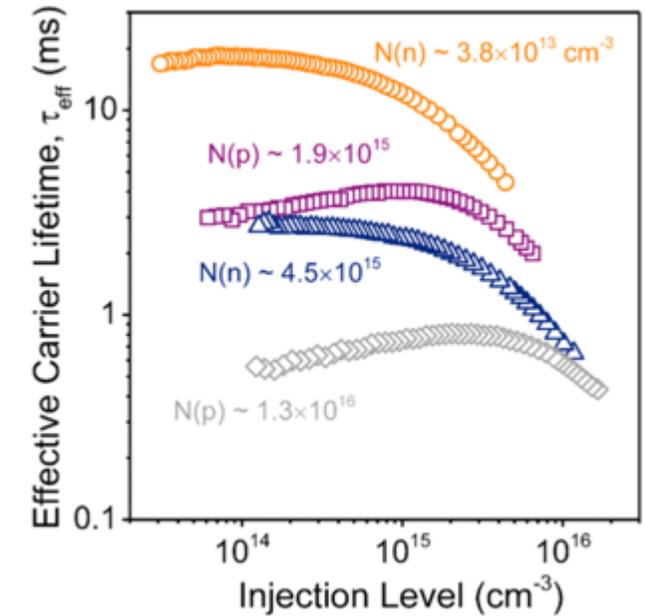
Motivation for Room Temperature Surface Passivation

- Room temperature, low-cost alternatives to expensive deposition tools
- Some examples:
 - Acid, halogen-alcohol, benzyl-alcohol, **organic thin-film**
- Thin film passivation: easy handling and good short-term stability for bulk characterization such as lifetime and PL
- Poly(tetrafluoroethylene) based polymer was explored recently for passivation of c-Si^[1-3]

[1]. D. Biro et al., *Solar Energy Materials and Solar Cells*, vol. 71, no. 3, pp. 369-374, 2002

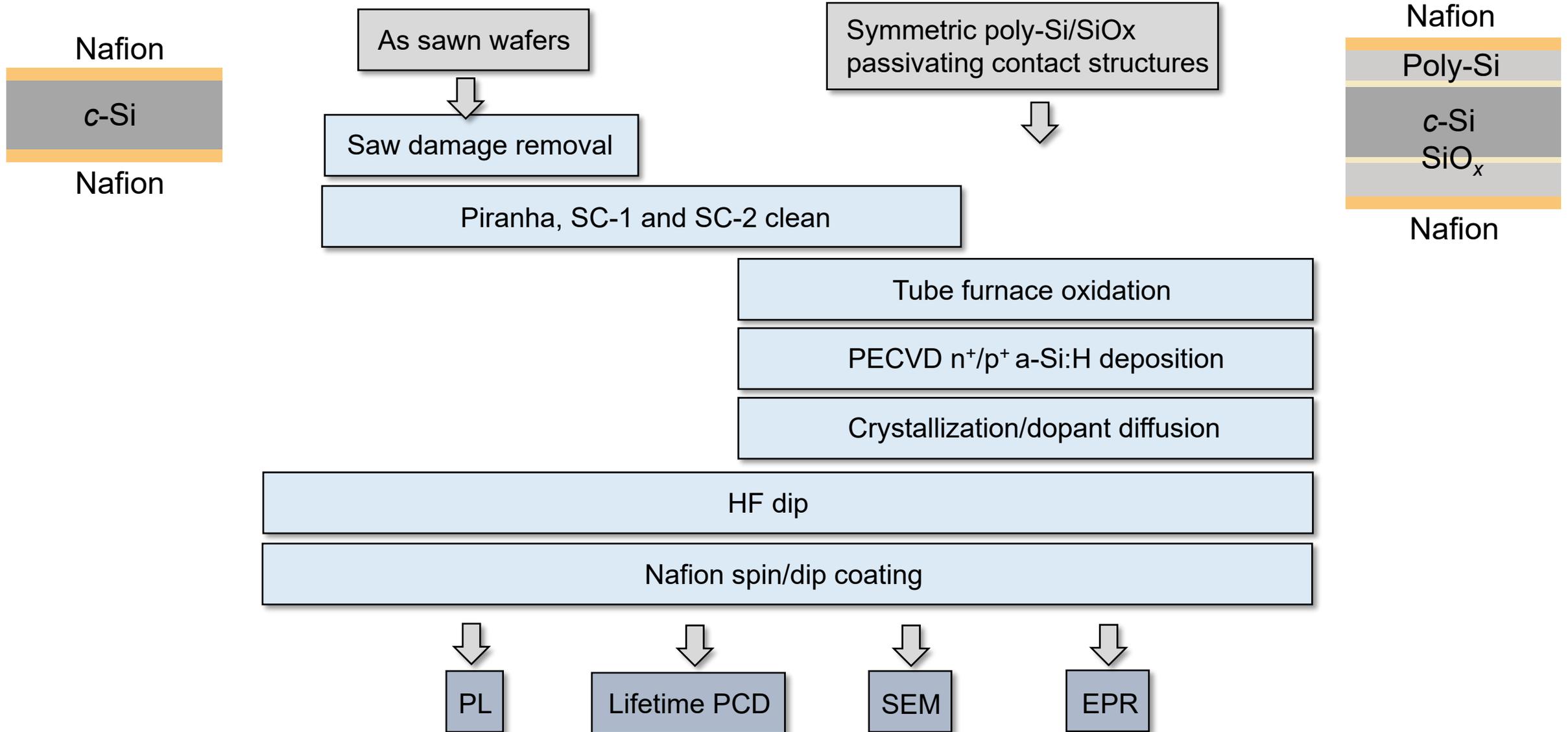
[2]. J. Chen et al., *ACS Applied Materials & Interfaces*, vol. 10, no. 51, pp. 44890-44896, 2018

[3]. W. Ji et al., *ACS Nano*, vol. 13, no. 3, pp. 3723-3729, 2019



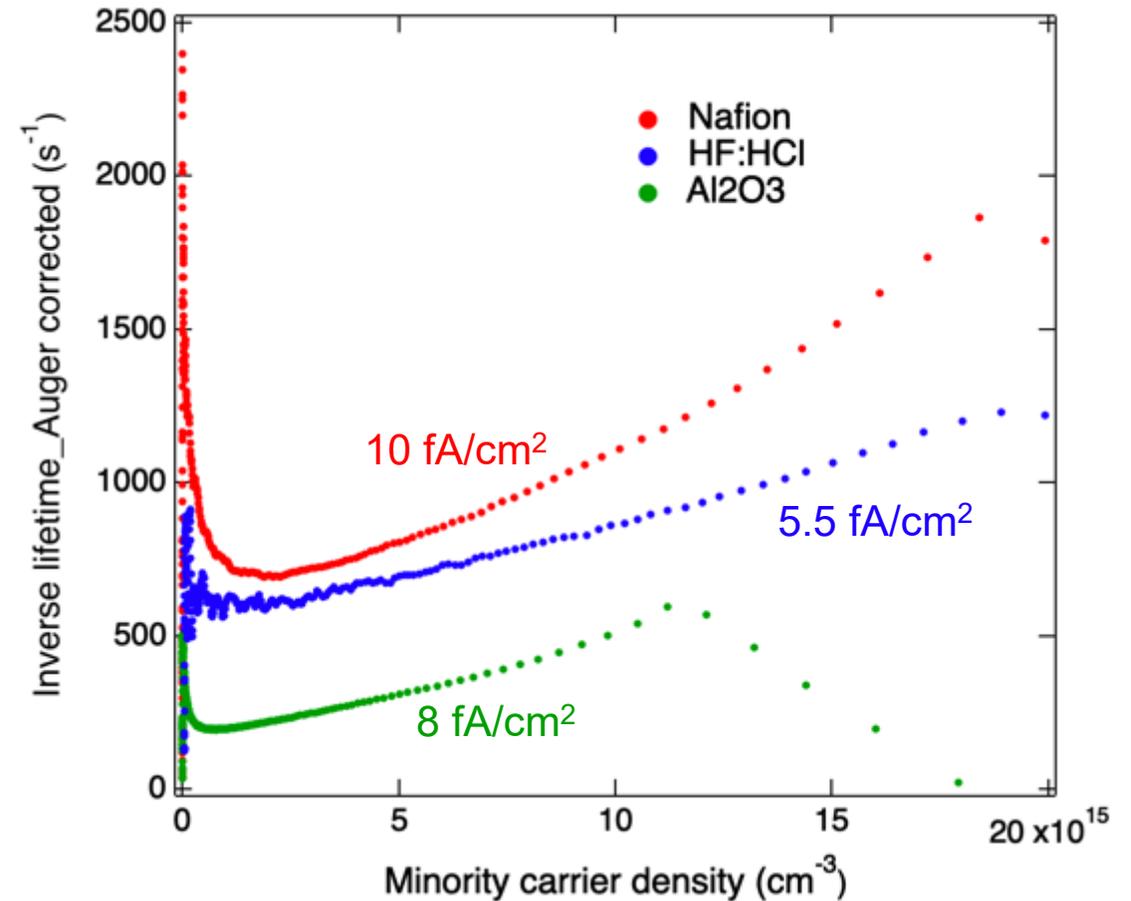
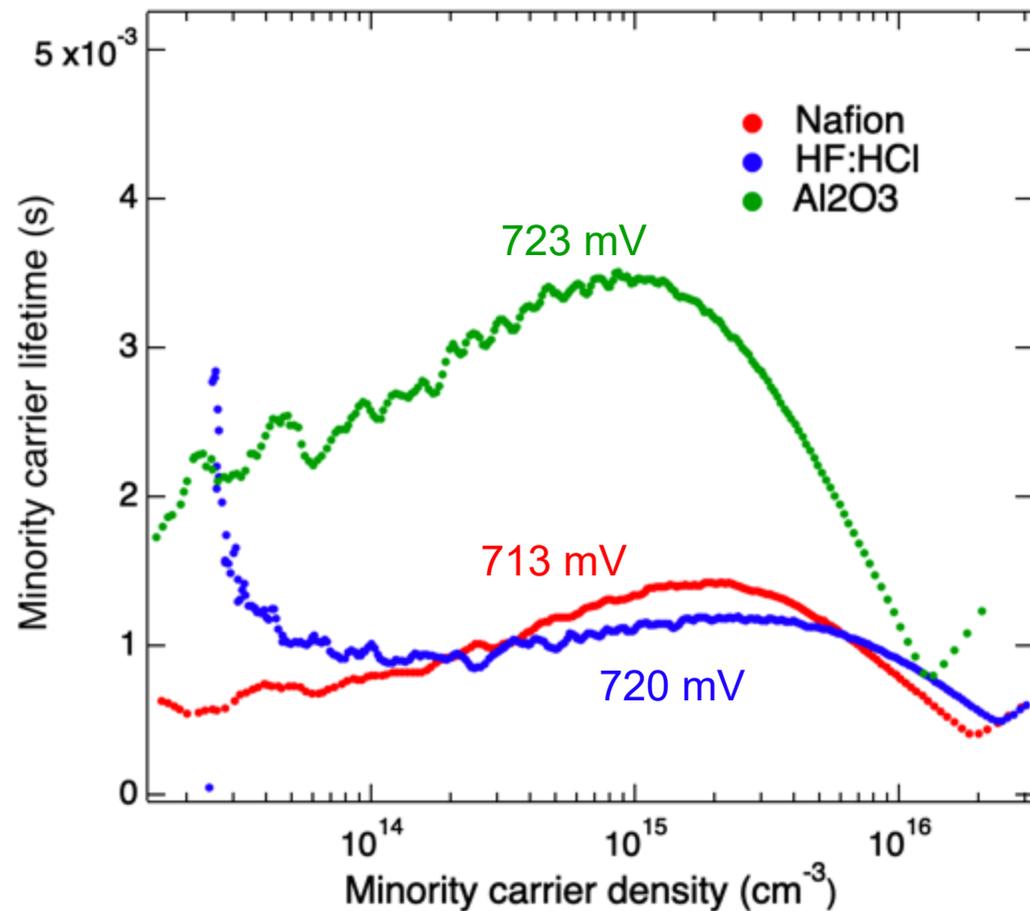
Nafion is a **room-T** technique, which is ideal for characterizing bulk defects using spectroscopy techniques such as Electron Paramagnetic Resonance (EPR)

Nafion Passivation Procedure at NREL



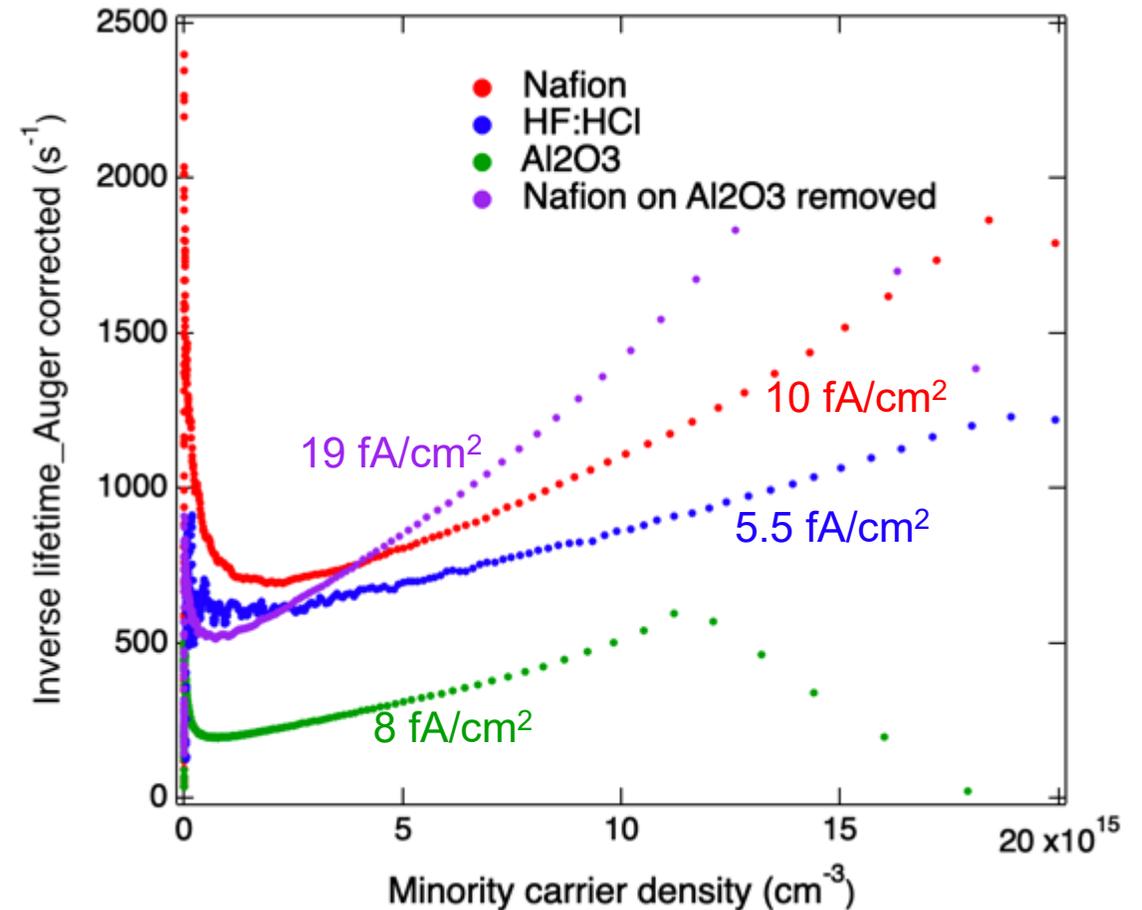
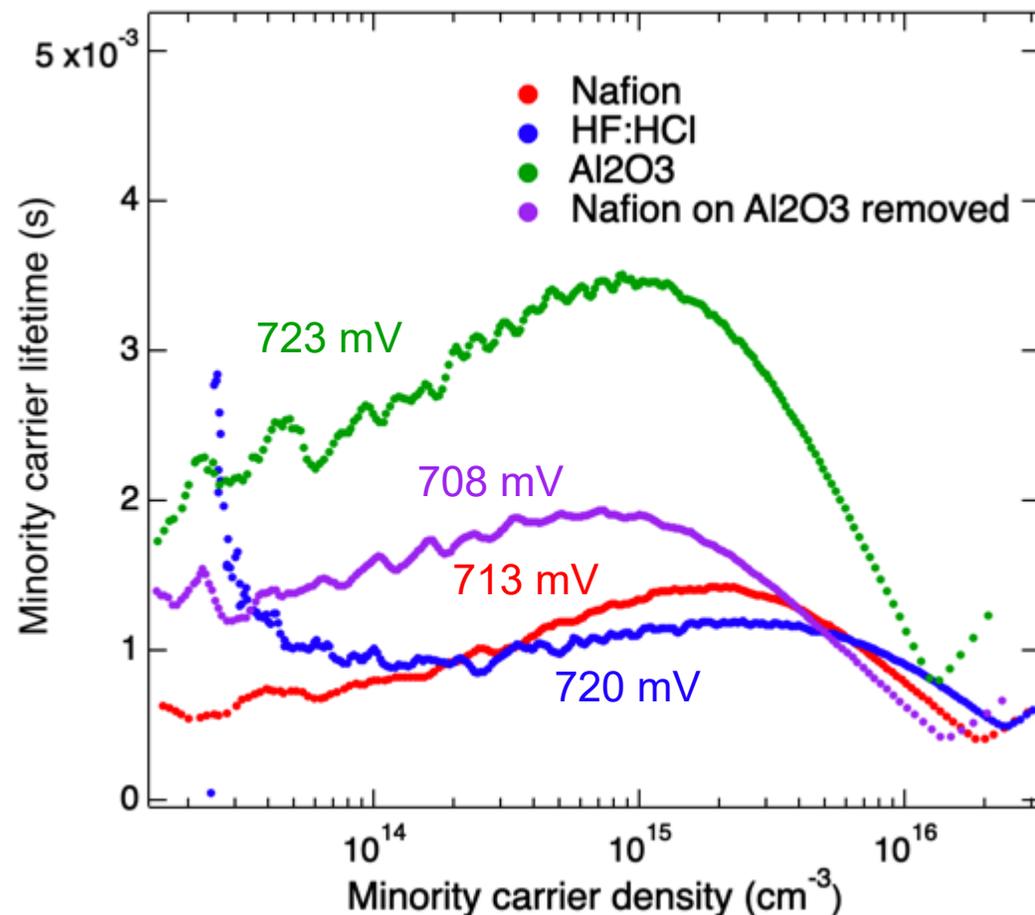
Passivation Results on *n*-type Cz Comparison

- Nafion passivation is comparable to HF:HCl liquid passivation in *n*-Cz wafer, but has a lower lifetime than Al₂O₃
- Slightly higher J_0 value was observed with Nafion dipcoat, but low enough for good passivation



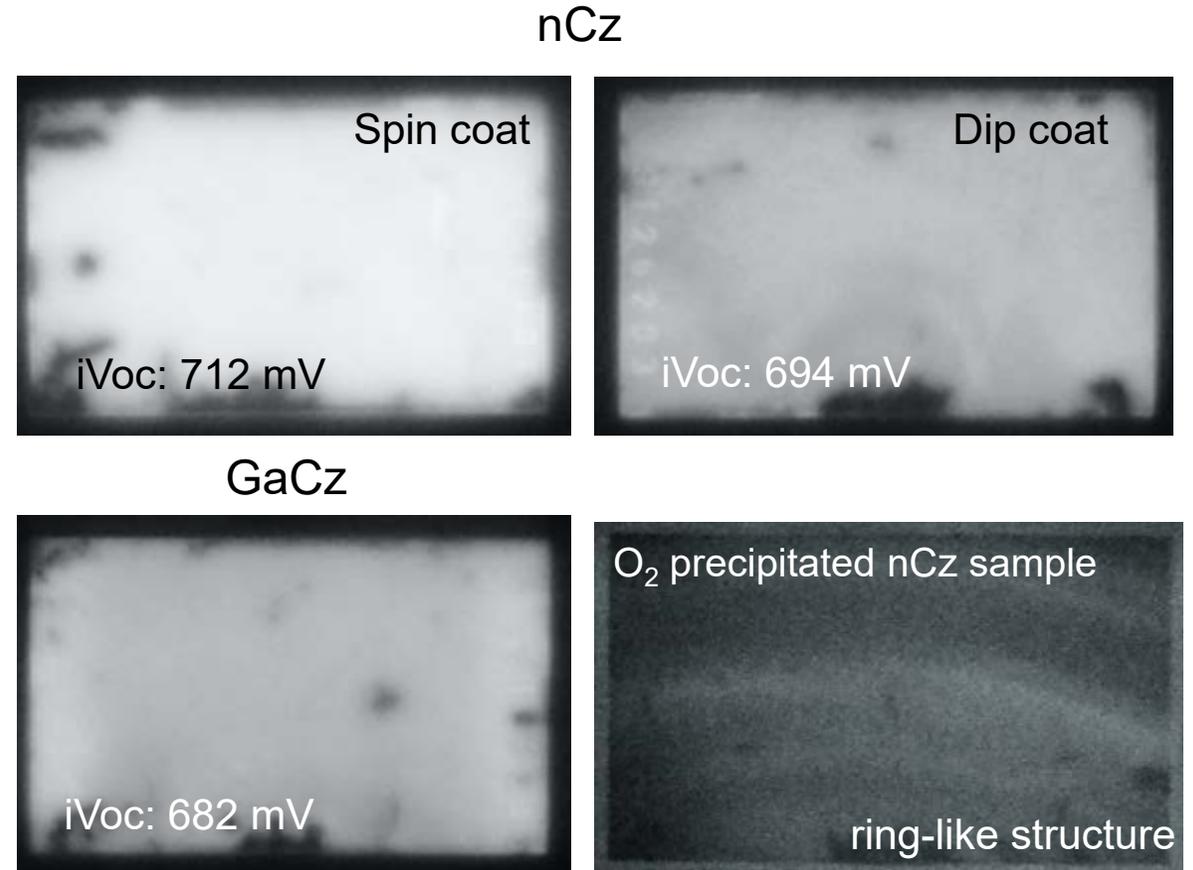
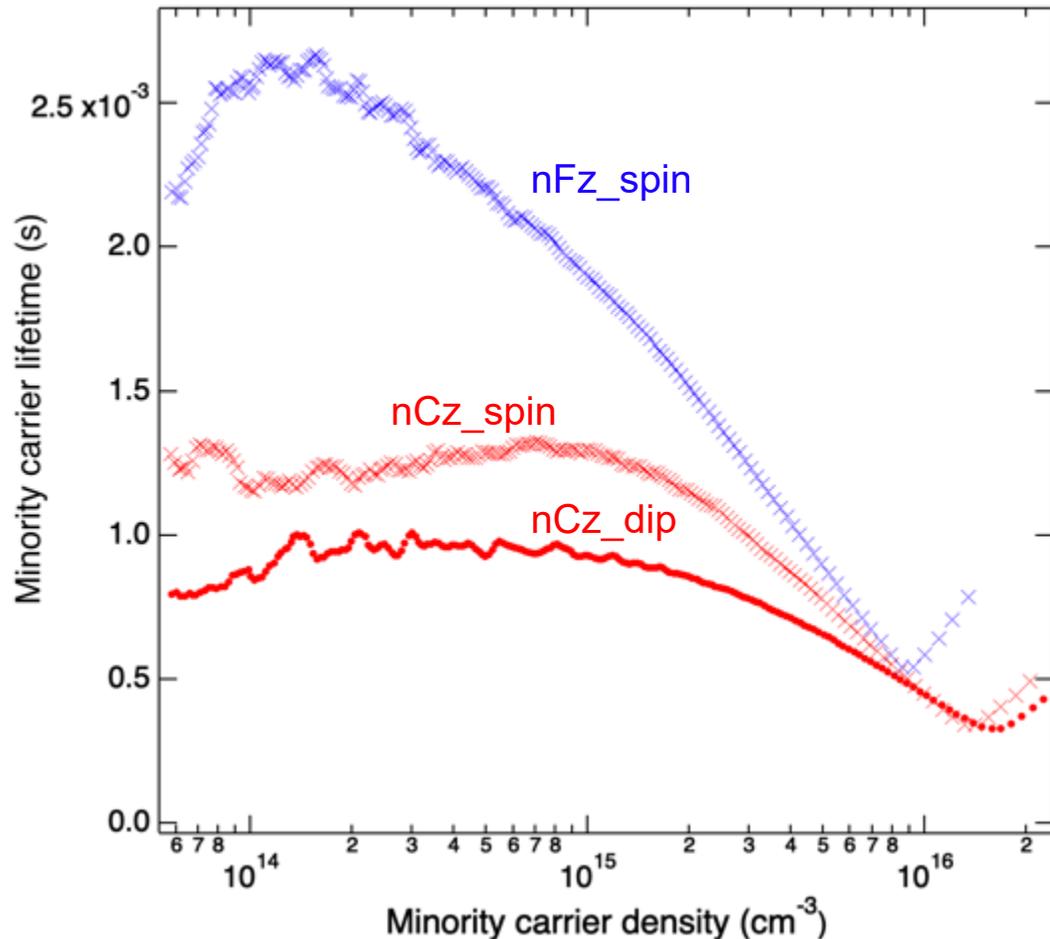
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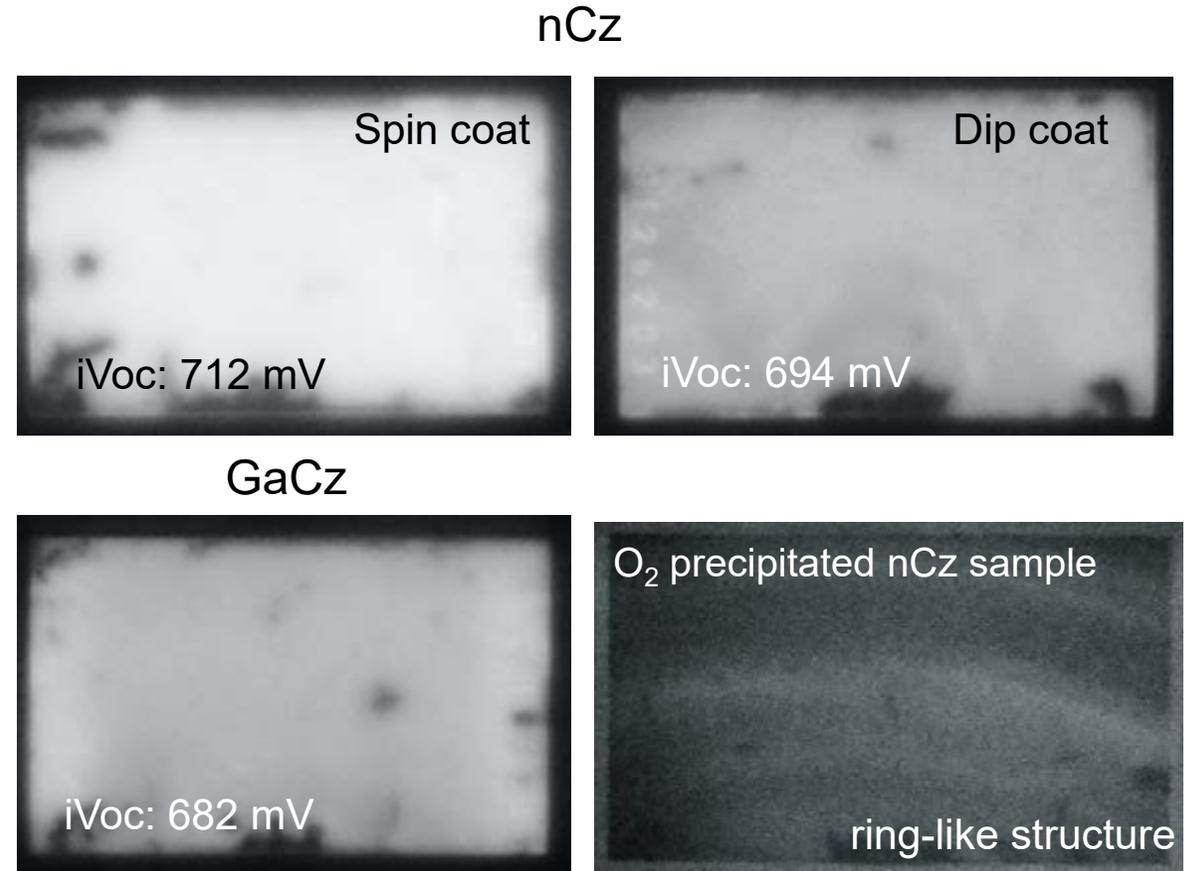
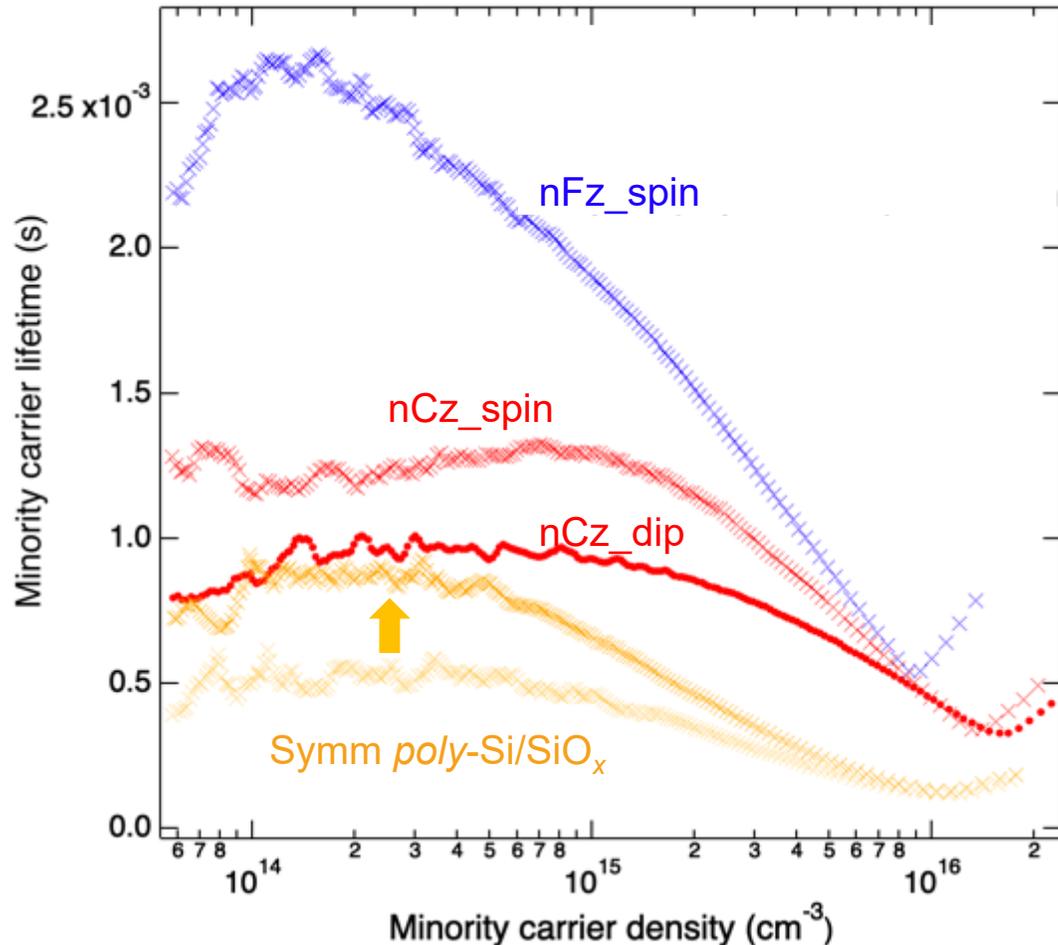
Passivation Results on Various Substrates

- *n*-type substrate has the highest passivation due to negative fixed charge from the strong Lewis acidity
- *n*- and *p*-type passivating contacts (200 nm *poly*-Si), and surface with oxide blocks field effect passivation
- Spin coating provided better uniformity and thinner films, which resulted in higher passivation quality



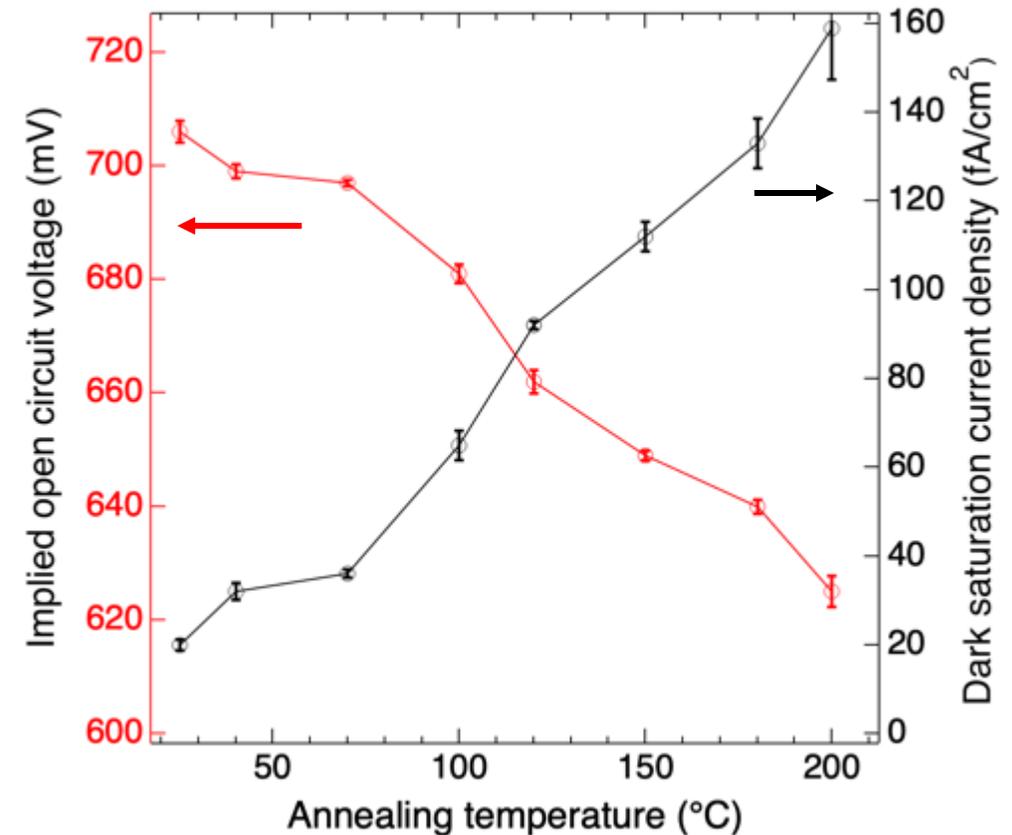
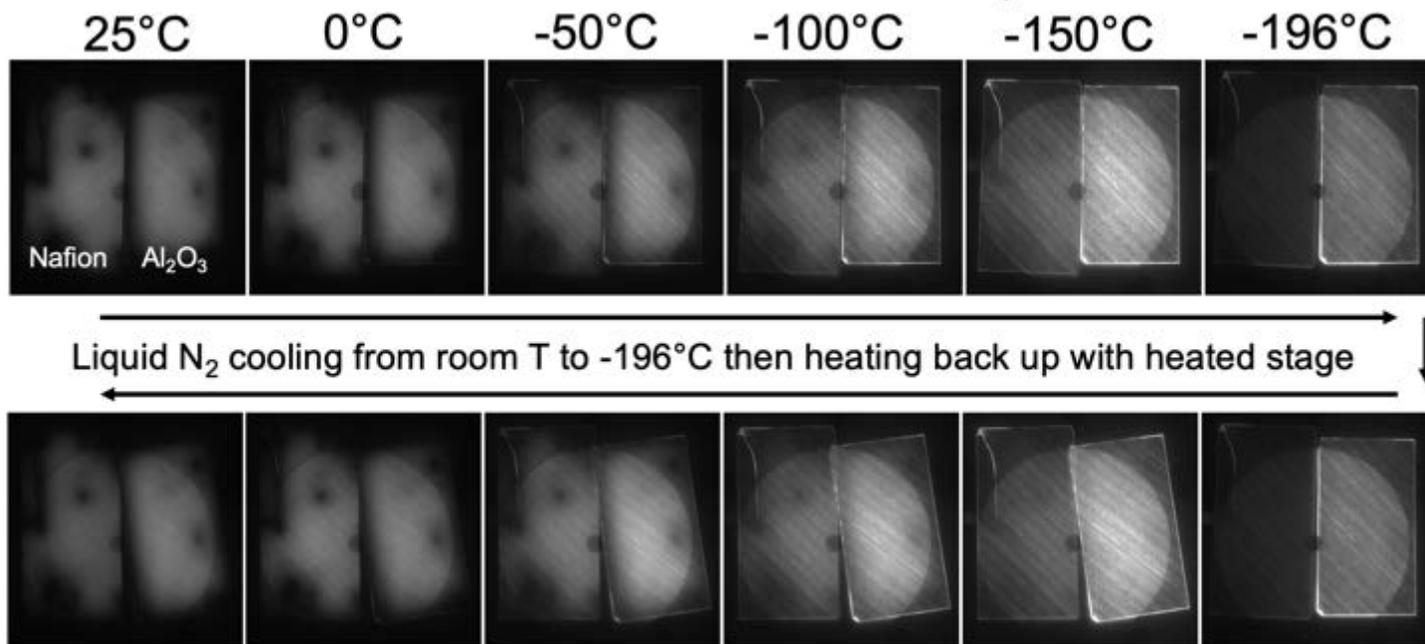
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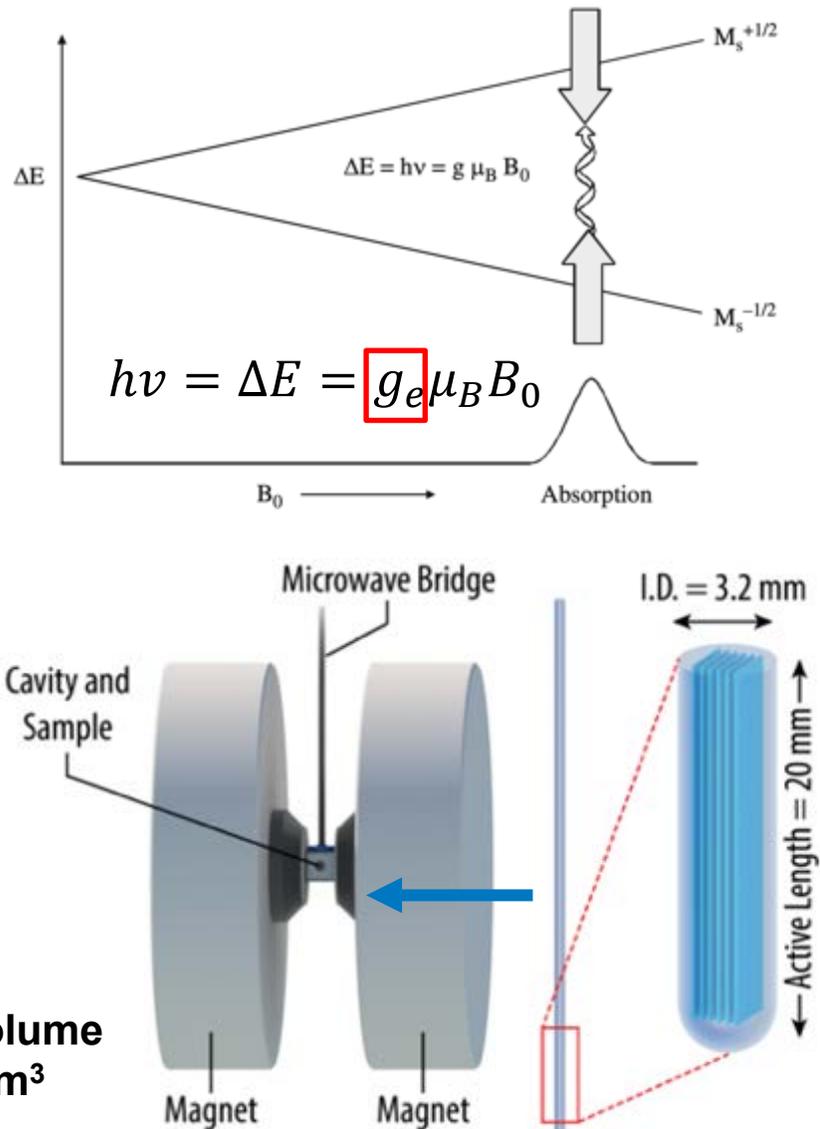


Temperature Dependency of Nafion Passivation

- Low T PL shows that Nafion can maintain a good passivation on c-Si samples up to -150°C , and the process can be reversed to room T with no passivation loss
- Nafion passivation decreases with increasing annealing temperature, but still remain some passivation at elevated T



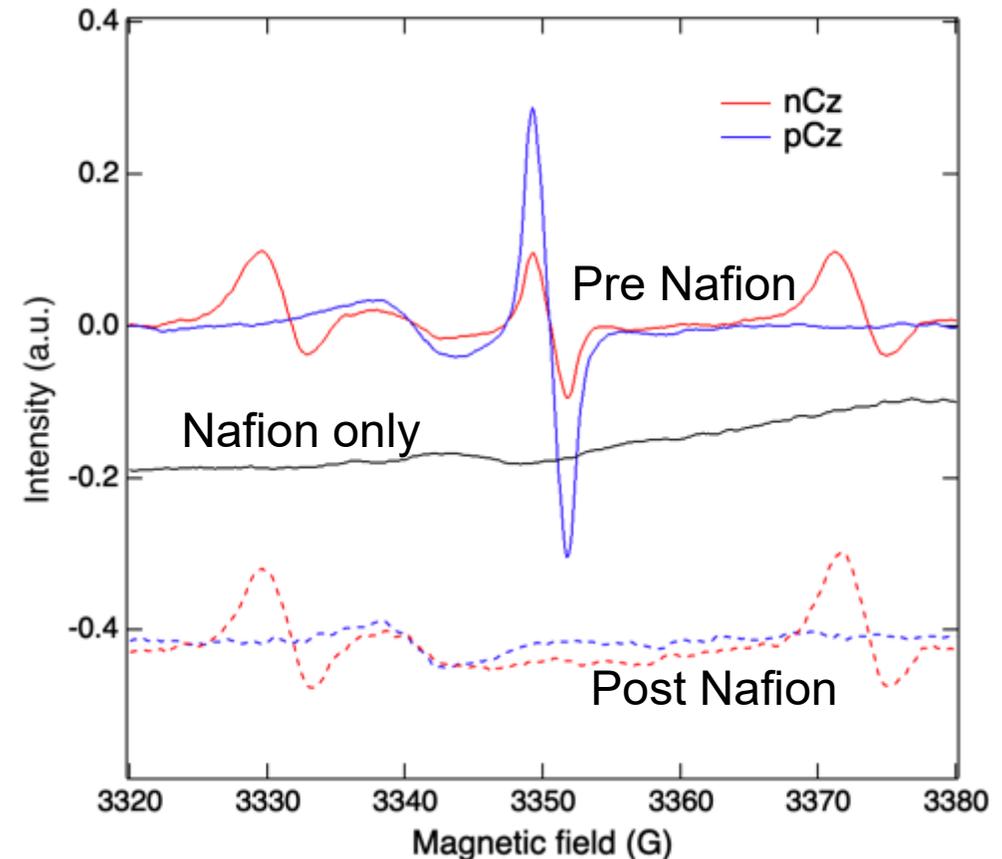
Electron Paramagnetic Resonance (EPR) of Nafion Passivation



Sample Volume
 ~0.01 cm³

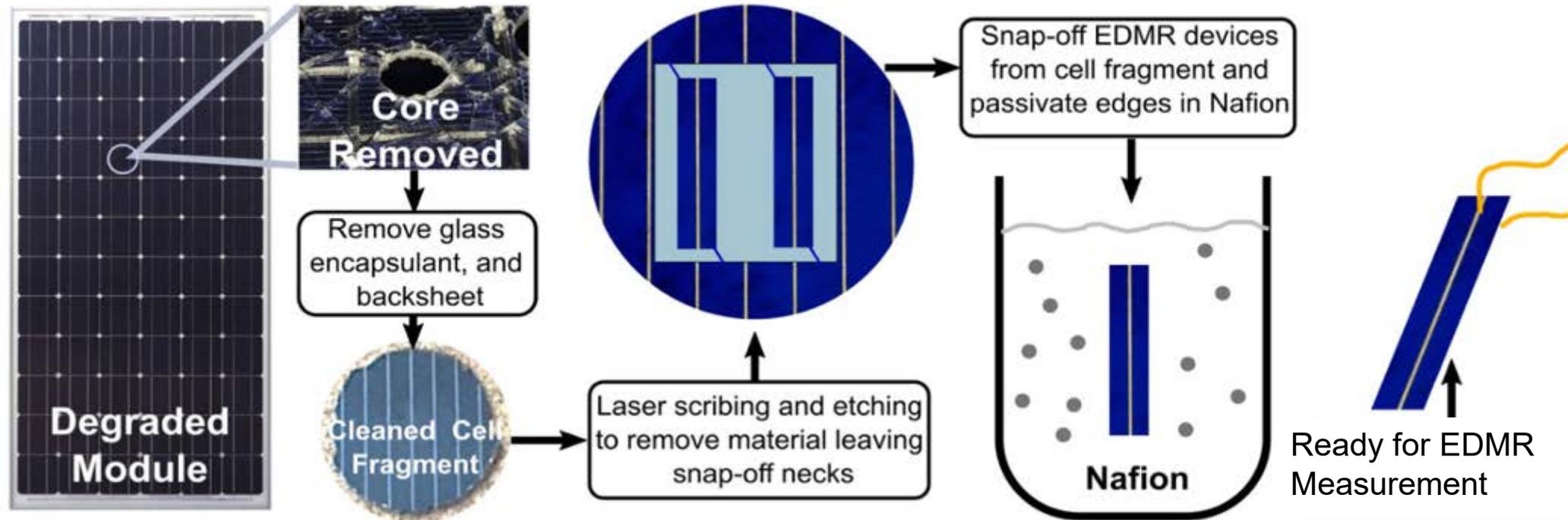
A. R. Meyer *et al.*, under review at *Joule*, (2022)

- We show for the first-time temperature study for Nafion down to 6K using EPR technique
- Both *nCz* and *pCz* samples have reduced peak ~3350G post Nafion



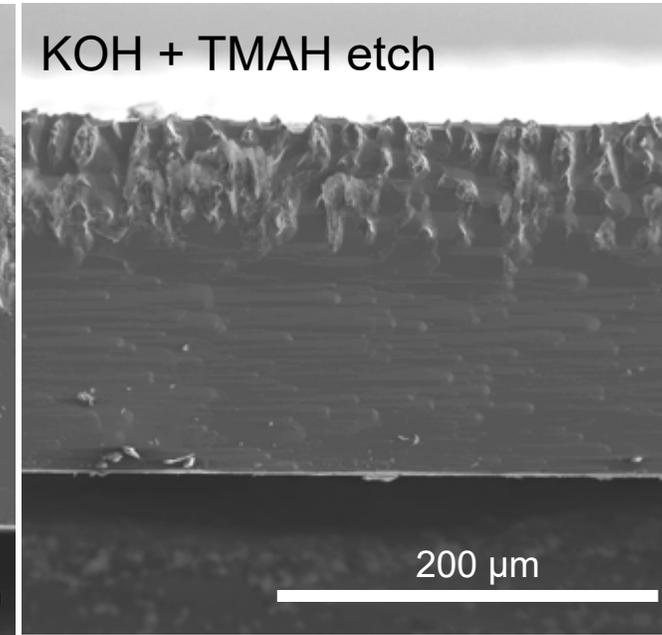
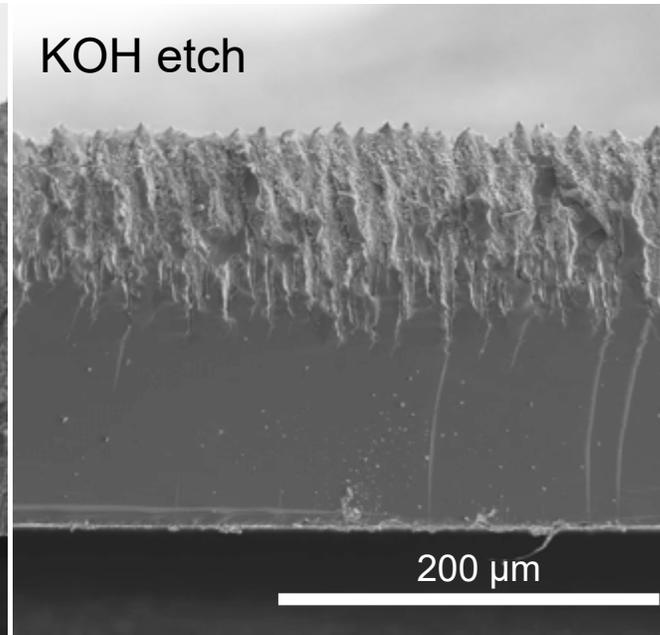
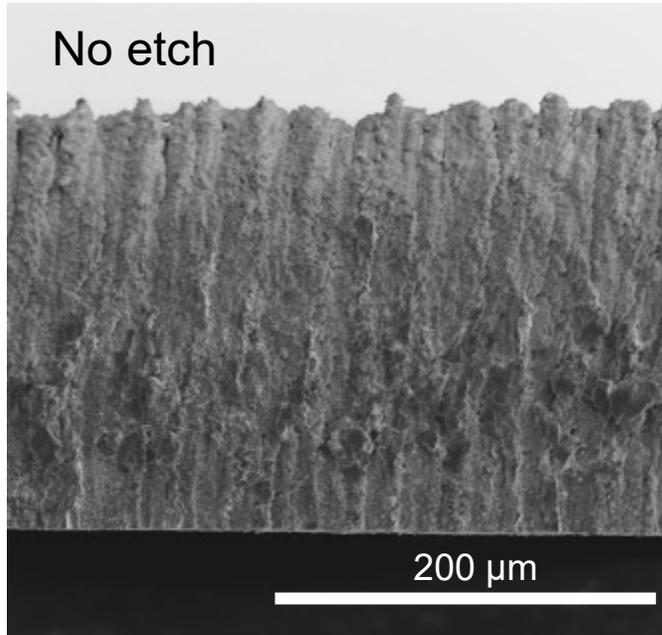
Nafion Passivation on Cell Fragment for EDMR Analysis

- Electrically detected magnetic resonance (EDMR) detects paramagnetic defects that affects the device's PV performance (sensitive to $\sim 10^9 \text{ cm}^{-3}$ defects)
- Laser-scribed small specimens are needed for characterizations such as EDMR



The Effect of Surface Morphology on Nafion Passivation Quality

- Surface morphology is closely related to the Nafion passivation quality
- Pretreatment (alkaline etching and clean) is required before Nafion to remove edge damage



Prototype EDMR structure passivated with Nafion

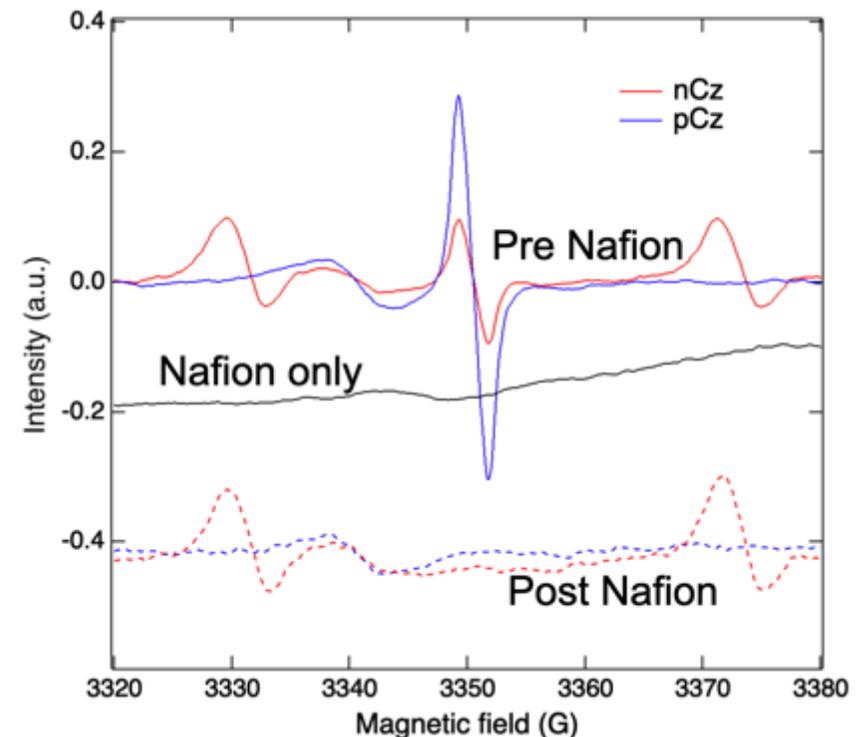


Summary and Conclusions

- Nafion is a promising room T, temporary passivation technique, which is ideal for bulk characterization of *n*-type *c*-Si
- Passivation can be used at low T with good passivation, and is compatible with cryogenic T of various characterization methods
- Surface etching of as-sawn *c*-Si is necessary before Nafion to obtain uniform passivation to sample edges

Advantages when introduced to PV applications:

- High throughput for wafer quality check
- Reduce process complexity and avoid hazardous materials
- Ideal for bulk degradation study



Acknowledgements

NREL Silicon Photovoltaic Team

- Dr. Paul Stradins
- Dr. David L. Young
- Bill Nemeth
- San Theingi
- Vinnie LaSalvia
- Matthew Page
- Markus Kaupa
- Dr. Chun-Sheng Jiang
- Dr. Harvey Guthrey
- Dr. Steven Harvey
- Dr. Suchismita Mitra

U.S. Department of Energy

Funding provided by U.S. DOE under Contract No. DE-AC36-08GO28308 and by U.S. DOE Office of Energy Efficiency and Renewable Energy Solar Energy Technologies Office under Agreement Number 3435. Additionally, this work was partially supported by the University of Padova (grant UNIPD-ISR 2017 'SENSITISE').

Dr. Sumit Agarwal's Research Group:

- Matthew B. Hartenstein
- Caroline Lima Salles
- Xue Wang
- Andrew Kaye
- Dirk Steyn
- Chirag Mule

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- Dr. Abigail R. Meyer



Thanks for your attention! Questions?



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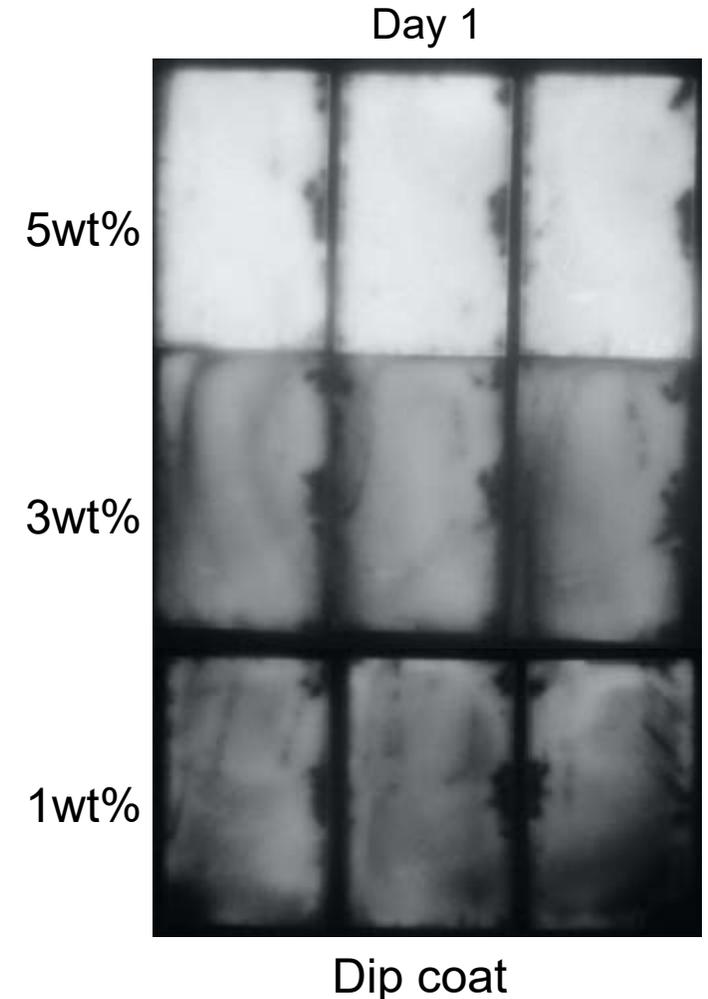
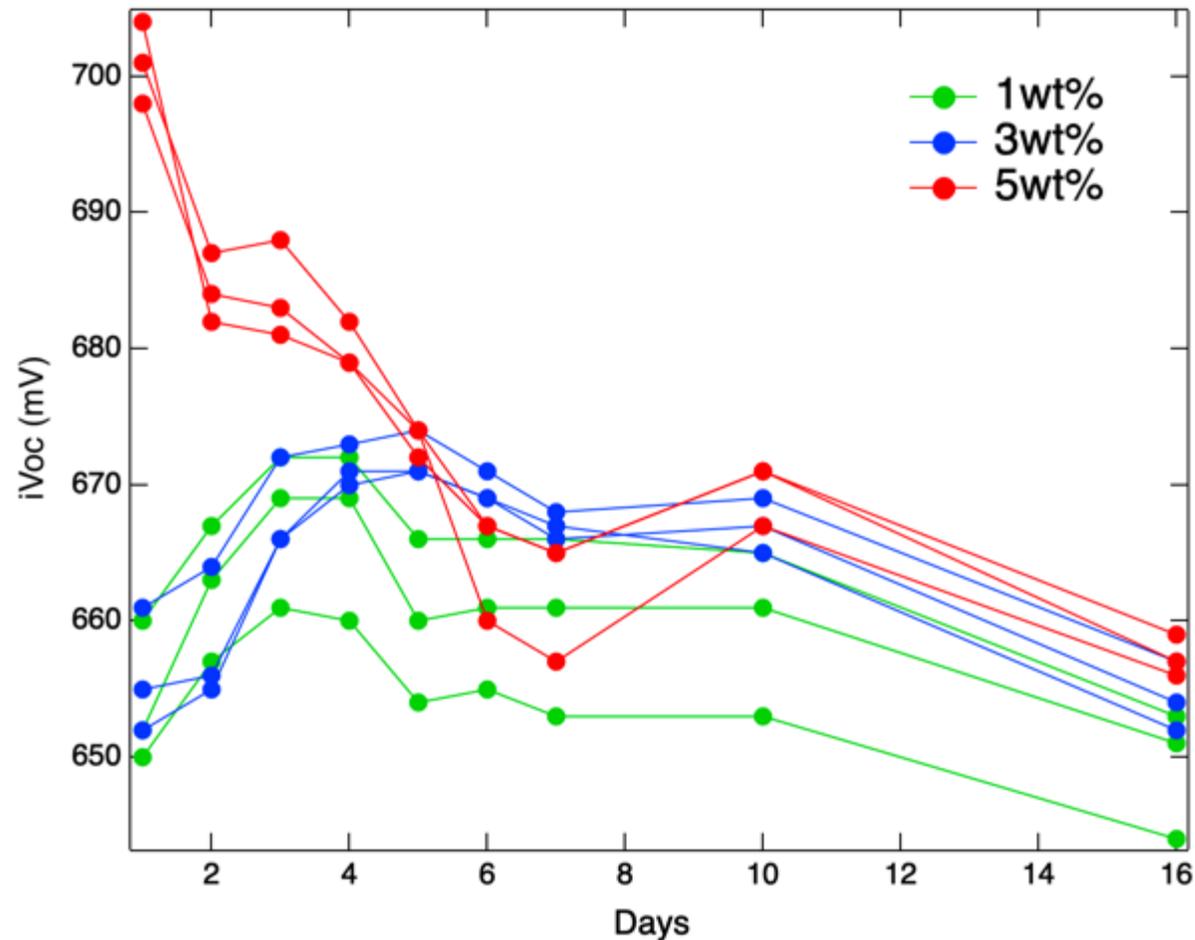
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Nafion Degradation Test with Different Concentrations

- 5 wt% of Nafion has the highest passivation quality on the day of, but quickly degrades after a day
- Nafion diluted with ethanol samples have slightly lower passivation but remained some passivation overtime



Humidity Effect on Nafion Passivation on *n*-type Cz

- Relative humidity between 48-70% has little effect on passivation quality

